REMARKS/ARGUMENTS

Favorable reconsideration of this application in view of the above amendment and following remarks is respectfully requested.

Claims 1, 2, 4-17, 20, and 21 are pending. Claims 13, 16, and 17 are withdrawn. In the present amendment, Claims 1 and 14 are amended. Support for the present amendment can be found in the original specification, for example, at page 21, lines 9-25, and in Claim 1. Thus, it is respectfully submitted that no new matter is added.

A complete response to the Office Action dated December 15, 2009, was filed on June 14, 2010, together with a Request for Continued Examination.

Applicants thank Examiner Parendo for the courtesy of an interview granted to Applicants' representative on June 30, 2010, at which time the outstanding issues in this case were discussed. The present response constitutes Applicants' statement of substance of the personal interview.

As the present Supplemental Amendment relates solely to the adoption of the Examiner's suggestions made during the interview, it is submitted the present Supplemental Amendment is fully compliant with 37 C.F.R. § 1.111(a)(2)(B), which allows for entry of Supplemental Responses that are clearly limited to the adoption of the Examiner's suggestions. *See* M.P.E.P. § 714.03(a). Accordingly, it is respectfully requested the present Supplemental Amendment be entered.

The present Supplemental Amendment amends Claim 1 to recite, in part, "after the forming the F-doped carbon film, modifying a chemical composition of said F-doped carbon film with radicals consisting of Ar and nitrogen." As discussed during the interview and acknowledged by Examiner Parendo, <u>Jiwari</u> does not disclose the chemical composition of the first fluorine containing organic film being later modified with radicals consisting of Ar and nitrogen. Instead, <u>Jiwari</u> merely describes a second fluorine-containing organic film

having no cavities being deposited on the first film having cavities. Accordingly, it is respectfully requested that the rejection of Claim 1, and all claims dependent thereon, as unpatentable over Tsai in view of <u>Jiwari</u>, be withdrawn.

Independent Claim 14 is amended to recite "a step of forming a stable compound of a metal fluoride by depositing a second metal film that reacts with F." As discussed during the interview and acknowledged by Examiner Parendo, <u>Ito</u> does not disclose or suggest that the Al film (asserted in the Office Action as corresponding to the claimed second metal film) reacts with F. Accordingly, it is respectfully requested that the rejection of Claim 14, and all claims dependent thereon, as unpatentable over <u>Ito</u> in view of <u>Sugahara</u>, be withdrawn.

Further, Claim 14 is amended to recite the feature of "said source gas has a F/C ratio larger than 1 and smaller than 2" from Claim 1 in order for Claim 14 to have unity of invention with Claim 1, as requested by Examiner Parendo in the interview.

For the reasons discussed in the present Supplemental Amendment and the Amendment filed on June 14, 2010, no further issues are believed to be outstanding in the present application, and the present application is believed to be in condition for formal allowance. Therefore, a notice of allowance is earnestly solicited.

Application No. 10/567,733 Supplemental Amendment to Amendment filed on June 14, 2010

Should the Examiner deem that any further action is necessary to place this application in even better form for allowance, the Examiner is encouraged to contact Applicants' undersigned representative at the below-listed telephone number.

Respectfully submitted,

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